	Application No.	Applicant(s)
Notice of Allowability	10/826,800	SNYDER ET AL.
	Examiner	Art Unit
	David Nhu	2818
The MAILING DATE of this communication app All claims being allowable, PROSECUTION ON THE MERITS IS	ears on the cover sheet w	ith the correspondence address
herewith (or previously mailed), a Notice of Allowance (PTOL-85 NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT R of the Office or upon petition by the applicant. See 37 CFR 1.31:) or other appropriate commated () or other appropriate commates () or other application is	unication will be mailed in due course. THIS
1. This communication is responsive to <u>11/2/06</u> .		
2. X The allowed claim(s) is/are 21-23 and 26-29.		
3. ☑ Acknowledgment is made of a claim for foreign priority u a) ☐ All b) ☐ Some* c) ☐ None of the:	nder 35 U.S.C. § 119(a)-(d)	or (f).
1. Certified copies of the priority documents have	e been received.	
2. Certified copies of the priority documents have		on No. <u>10/461,291</u> .
3. Copies of the certified copies of the priority do		
International Bureau (PCT Rule 17.2(a)).		
* Certified copies not received:		
Applicant has THREE MONTHS FROM THE "MAILING DATE" noted below. Failure to timely comply will result in ABANDONN THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.	of this communication to file MENT of this application.	e a reply complying with the requirements
 A SUBSTITUTE OATH OR DECLARATION must be subm INFORMAL PATENT APPLICATION (PTO-152) which giv 	nitted. Note the attached EX es reason(s) why the oath o	AMINER'S AMENDMENT or NOTICE OF or declaration is deficient.
5. CORRECTED DRAWINGS (as "replacement sheets") mu	st be submitted.	· .
(a) including changes required by the Notice of Draftspers		w (PTO-948) attached
1) 🗌 hereto or 2) 🔲 to Paper No./Mail Date		
(b) ☐ including changes required by the attached Examiner' Paper No./Mail Date	's Amendment / Comment o	r in the Office action of
Identifying indicia such as the application number (see 37 CFR 1 each sheet. Replacement sheet(s) should be labeled as such in the same of	l.84(c)) should be written on the header according to 37 C	the drawings in the front (not the back) of FR 1.121(d).
 DEPOSIT OF and/or INFORMATION about the deposit attached Examiner's comment regarding REQUIREMENT 	sit of BIOLOGICAL MAT FOR THE DEPOSIT OF BI	ERIAL must be submitted. Note the OLOGICAL MATERIAL.
Attachment(s)		
1. Notice of References Cited (PTO-892)	5. Notice of Ir	nformal Patent Application
2. Notice of Draftperson's Patent Drawing Review (PTO-948)	6. Interview S	iummary (PTO-413), /Mail Date
Information Disclosure Statements (PTO/SB/08), Paper No./Mail Date		Amendment/Comment
 Examiner's Comment Regarding Requirement for Deposit of Biological Material 		Statement of Reasons for Allowance
	9. 🗌 Other	
	\nearrow	Sera

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REASONS FOR ALLOWANCE

1. Claims 21-23, 26-29 are allowed.

- The following is an examiner's statement of reasons for allowance: None of the references of record teaches or suggests as cited in claims 21, 23: a perimeter of a first intermatallic mixture interposed between the first and the second wafers, the first intermetallic mixture comprising materiall from a first reactive foil and a first bonding material, the first intermetallic mixture being formed after a first exothermic reaction of the first reactive foil; a device; and a second intermetallic mixture interposed between the device and the first wafer, the second intermetallic mixture comprising materials from a second reactive foil and a second bonding material, the second intermetallic mixture being formed after a second exothermic reaction of the second reactive foil (as cited in claim 21); a perimeter of a first intermatallic mixture interposed between the first and the second wafers, the first intermetallic mixture comprising materiall from a first reactive foil and a first bonding material, the first intermetallic mixture being formed after a first exothermic reaction of the first reactive foil; a third wafer; and a second intermetallic mixture interposed between the second and the third wafers, the second intermetallic mixture comprising materials from a second reactive foil and a second bonding material, the second intermetallic mixture being formed after a second exothermic reaction of the second reactive foil (as cited in claim 23):
- 3. Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

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CONCLUSION

4. The prior art made of record and not relied upon is considered pertinent to applicant's disclosure: Lin et al (6,232,150 B1): Process for Making Microstructures and Microstructures Made thereby

5. Any inquiry concerning this communication on earlier communications from the examiner should be directed to David Nhu, (571)272-1792. The examiner can normally be reached on Monday-Friday from 7:30 AM to 5:00 PM.

The fax phone number for the organization where this application or proceeding is assigned is (571)273-8300.

David Nhu

November 27, 2006

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